Positioning and Manipulating Single Dopant Atoms inside Silicon

Andrew R. Lupini, Bethany M. Hudak, Jiaming Song, Hunter Sims, M. Claudia Troparevsky, Sokrates T. Pantelides and Paul C. Snijders

The ability to controllably position single atoms inside materials could enable production of a new generation of atomically precise artificial materials with direct relevance for many areas of technology. For example, spins from individual donors in a semiconductor comprise one of the most promising architectures for quantum computing. However, fabrication of the 'qubits' that would make up a quantum computer is still unreliable and many fundamental materials science questions remain unanswered. Perhaps the key technical difficulty is the task of accurately positioning single atom dopants inside a solid with control, or at least understanding, of their local environment.

Silicon is the ideal substrate to explore such ideas because of the ability to obtain isotopically purified samples (a "spin-vacuum") and compatibility with existing electronic components and manufacturing technologies. Group V elements are promising candidates for use as single-atom qubit dopants in Si, and it has recently been argued that bismuth could be an excellent dopant for such applications, because of its anomalously high spin-orbit coupling. Bi, in particular, has a large atomic number relative to Si, making it an ideal candidate to study using Z-contrast scanning transmission electron microscope (STEM). However, both precise doping and the imaging of single dopant atoms present many scientific challenges. For example, Bi is not very soluble in Si, meaning that the dopant atoms tend to migrate out of position during sample growth.

Here we will show examples of sample growth including novel nanostructures and single atom dopants. We will show dopant atoms imaged inside Si samples, and demonstrate electron-beam directed movement of single dopants.

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